



<b>Session Title:</b>	<b>[TF1] Frontier Metrology and Modeling III</b>
<b>Session Date:</b>	<b>November 21 (Tue.), 2023</b>
<b>Session Time:</b>	<b>08:30-09:50</b>
<b>Session Room:</b>	<b>Room F (Sicily Room, 1F)</b>
<b>Session Chair:</b>	<b>Prof. Mohit Kumar (Ajou Univ., Korea)</b>

**[TF1-1] [Invited] 08:30-09:00**

**Important Role of Nano-Scale Metrology for Next Generation Device Manufacturing**

Jae-hyun Kim (SK hynix, Korea)

**[TF1-2] [Invited] 09:00-09:30**

**Spectroscopically Resolved Electronic Band Structures of Ultrathin Oxide Layers and Interfaces for Advanced ICs and IGZO-Based TFTs**

Hyungtak Seo, Kumar Mohit, and Hyunmin Dang (Ajou Univ., Korea)

**[TF1-3] [Invited] 09:30-09:50**

**Comparative Electrical Characterization of High-K Dielectrics on Ge: Single and Stacked Structures Grown by H<sub>2</sub>O and O<sub>3</sub>-Based ALD**

Woohui Lee, Hyungshul Shin, Joohee Oh, Jinsung Park, and Hyounghsub Kim (Sungkyunkwan Univ., Korea)